

SMI

0981-HK

1995 1995

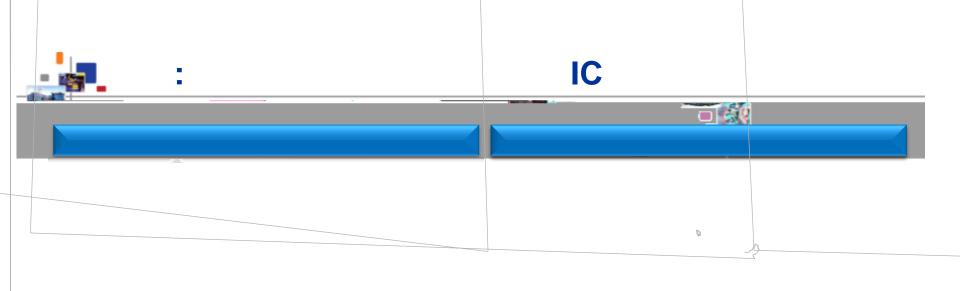
> 20-F 6-K





- 简介
- 口中芯业绩
- 口中国半导体行业机遇
- 口获





18.21% 17.50% 64.29%

> :4 ,4 ,2

: NASDAQ OMX , 2016 10 13 2016









2015 2009-2015

30

20

20

20

## **William Tudor Brown**

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30

Cadence Design Systems, Inc.

2008 2012

(NEA)









**2009 2015:** 

**2008 2009**:

**2002** 2008:





NEC **2009 2011:** 

■ 2007 2009: Silterra Malaysia

**2005** 2006: **2001 2005**:

**1996 2001:** 

■ 1984 1996: AT&T











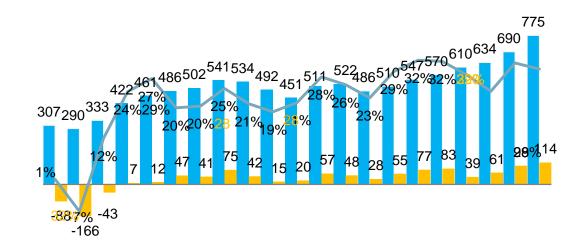




















		3	2016	
	45nm	20K	20K	~20K
	55-90nm, 0.13um	39K	45K	~50K
	45nm	15.5K	18K	~35K
(	0.11-0.35um	107K	108K	~108K
(	0.13-0.35um	45K	-	~45K
(	0.15-0.35um	31K	31K	~50K
6 (	90nm-0.18um	40K	-	~50K

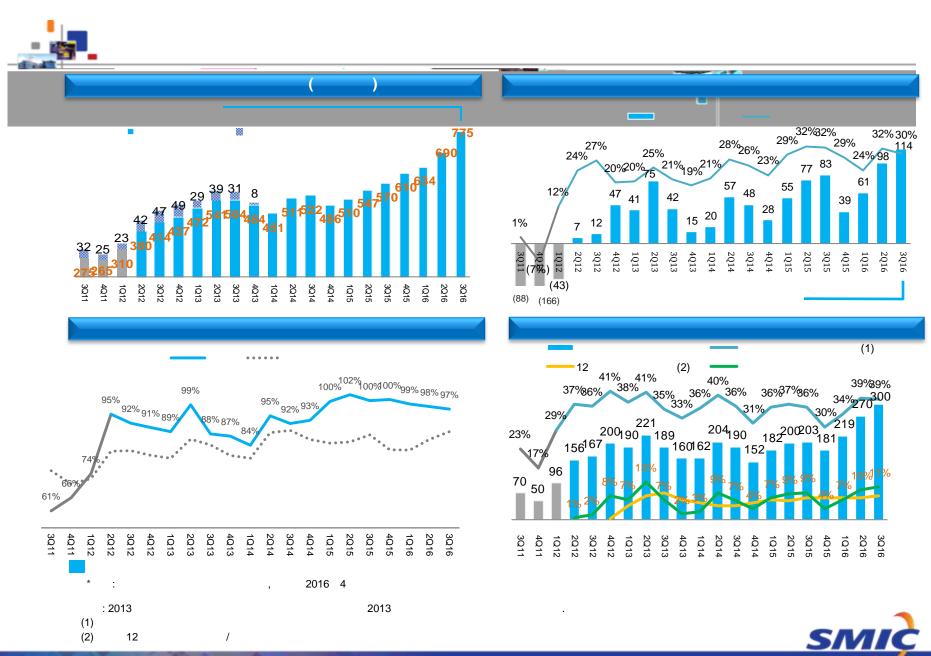


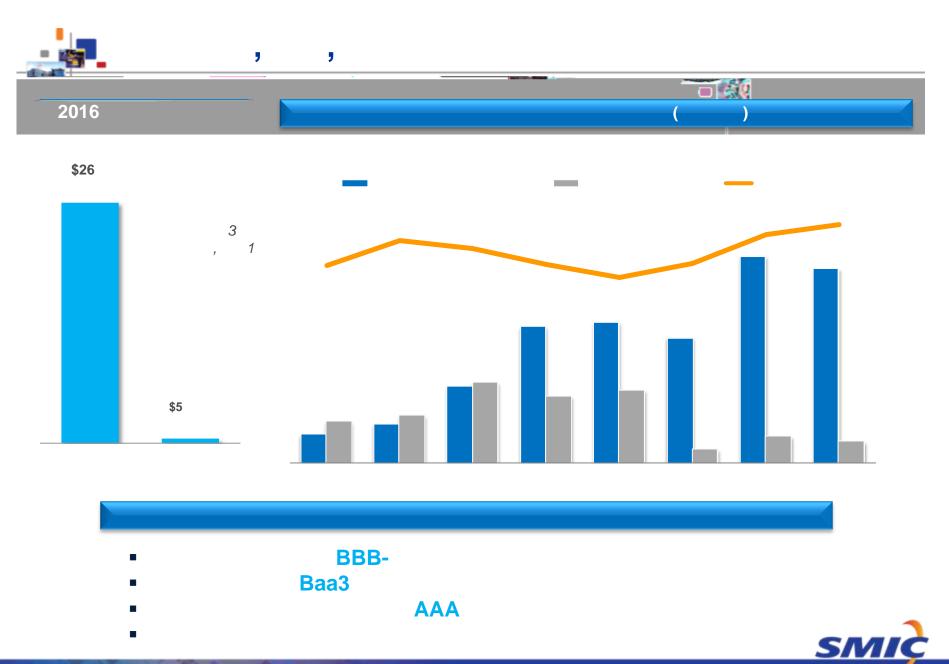




- 口简介
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- □获利成长战略
- □总结











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2015

## 2013~2015

39%

IF中代

HUAWEI

IENOVO联想

COOlpad 酷派

TCL

\*\*R 图 动 生 着
The Creative Life

TCL 常意动生活The Creative Life

Hisense
Skyworth

別選 KDNKA

Haier

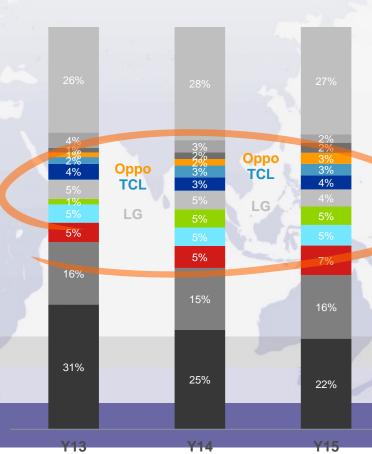
35%
5%
IEDOVO联想
TCL 创意感动生活 The Creative Life
HUAWEI
Www.teclast.com

21%

Ienovo联想

Haier

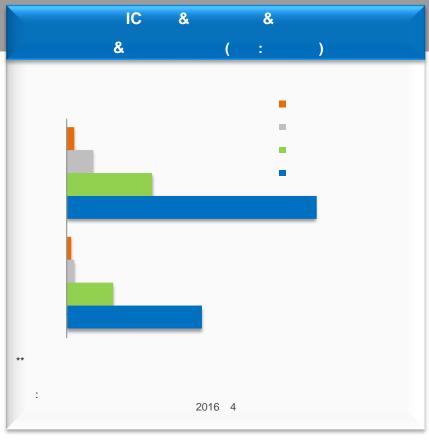
清华同方
TSINGHUA TONGFANG



: iSuppli, Gartner, FGI, GfK,

2016 3









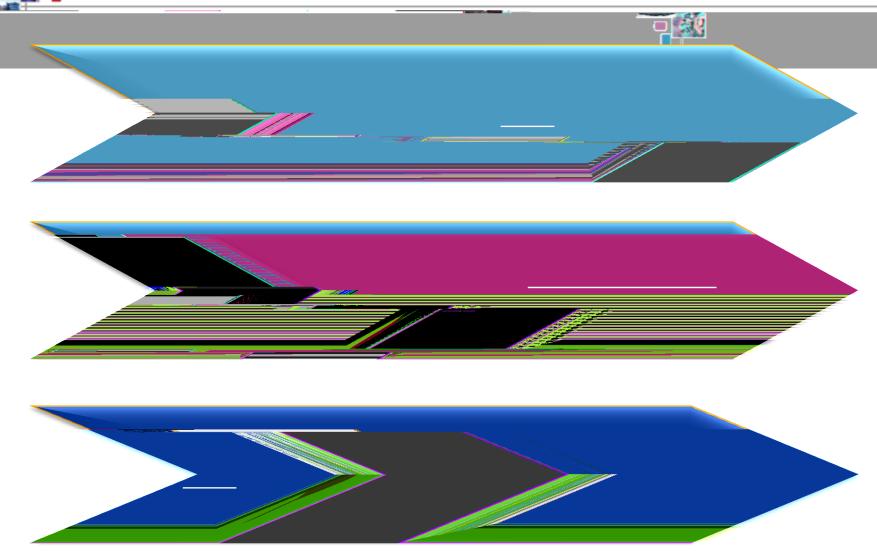


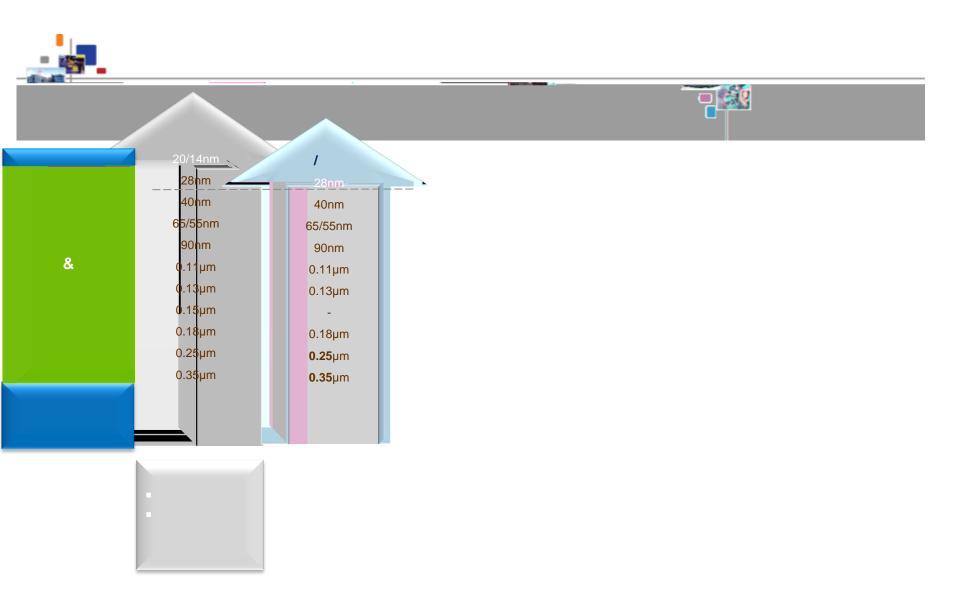


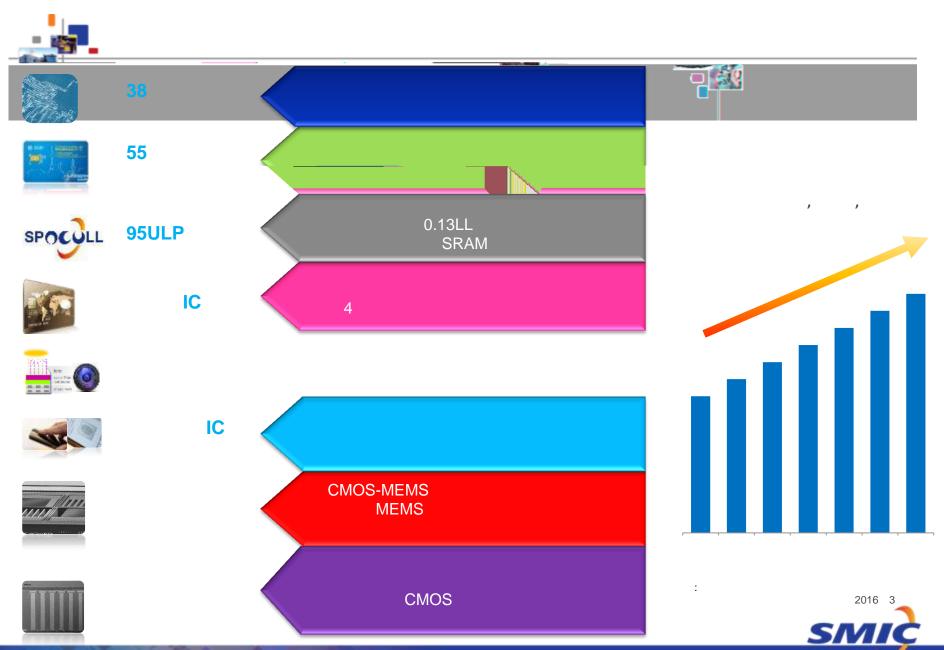
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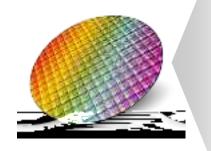










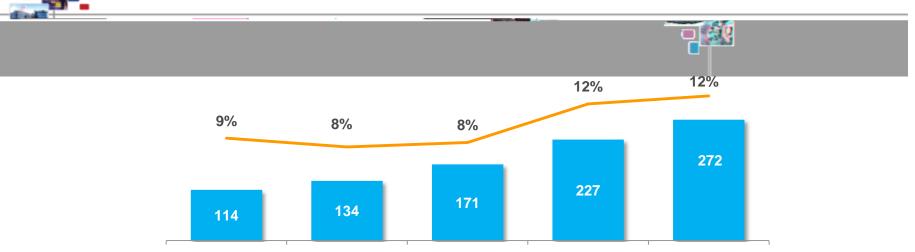


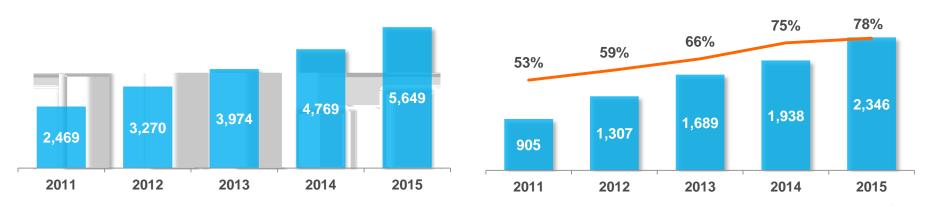
- 8 0.13LL 0.13LL SRAM

■ SPOCULL --- <u>SMIC POly Contact for Ultra Low Leakage</u>







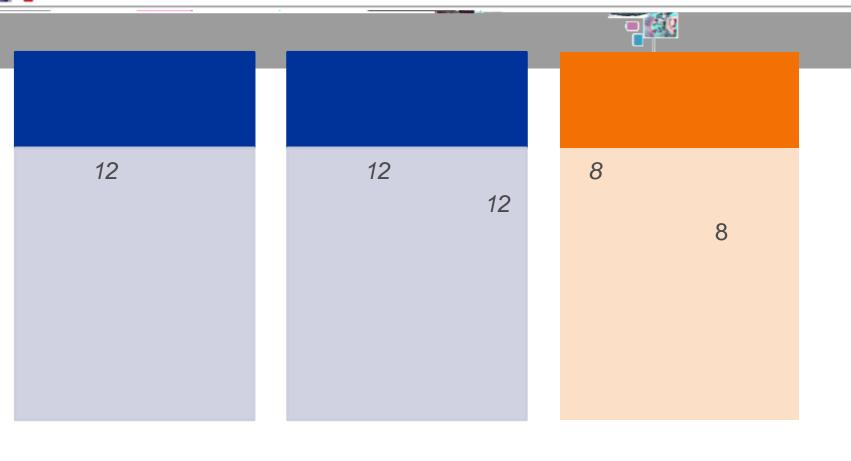




LFoundry 8 4900 33 9 **LFoundry 70% 11.8%** ( 2016 2







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- 口获利

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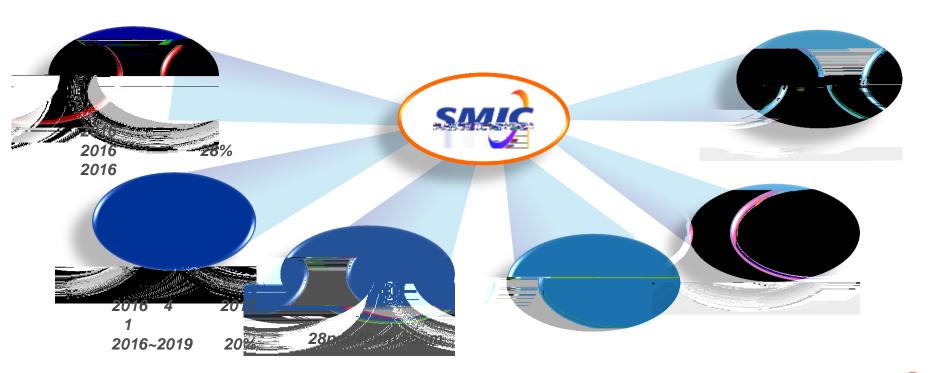






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: ir@smics.com

